

**AMENDMENTS TO THE CLAIMS**

Please **CANCEL** claims 28-30 without prejudice or disclaimer.

Please **AMEND** claims 27 and 31-34 as shown below.

Please **ADD** claims 47-48 as shown below.

The following is a complete list of all claims in this application.

1-26. (Cancelled)

27. (Currently Amended) A method for manufacturing a liquid crystal display (LCD),  
comprising steps of:

forming a color filter layer on a substrate;

forming a conductive layer on the color filter layer; and

~~forming a protrusion and a spacer on the conductive layer,~~

forming an organic insulating layer on the conductive layer, the organic insulating layer  
being photosensitive;

exposing the organic insulating film to a light beam through a mask having an opaque  
area, a semitransparent area and a transparent area on predetermined areas thereof; and

developing the organic insulating layer to form the protrusion and the spacer, wherein the  
~~protrusion and a spacer are formed of the same material and the spacer is taller than the~~  
protrusion.

28-30. (Cancelled)

31. (Currently Amended) The method of claim ~~30~~ 27, wherein the spacer is formed at a portion of the ~~photosensitive~~ organic insulating layer corresponding to the opaque ~~layer~~ area and the protrusion is formed at a portion of the ~~photosensitive~~ organic insulating layer corresponding to the semitransparent ~~pattern~~ area.

32. (Currently Amended) The method of claim ~~30~~ 27, wherein the spacer is formed at a portion of the ~~photosensitive~~ organic insulating layer corresponding to the transparent ~~layer~~ area and the protrusion is formed at a ~~photosensitive~~ portion of the organic insulating layer corresponding to the semitransparent ~~pattern~~ area.

33. (Currently Amended) ~~The~~ A method for manufacturing a liquid crystal display (LCD), of claim 27, wherein the step of forming the protrusion and the spacer comprises steps of: comprising steps of:

forming a color filter layer on a substrate;

forming a conductive layer on the color filter layer;

forming an insulating layer on the conductive layer;

forming a photoresist layer on the insulating layer; and

patterning the insulating layer and the photoresist layer to form the protrusion and the spacer, wherein the spacer is taller than the protrusion.

34. (Currently Amended) The method of claim 33, wherein the step of patterning the insulating layer and the photoresist layer comprising steps of:

preparing a mask ~~layer~~ having an opaque area, a semitransparent area and a transparent area on predetermined areas thereof;

exposing the photoresist layer to a light beam though the mask ~~layer~~;

developing the photoresist layer to expose portions of the insulating layer; and

etching the exposed portions of the insulating layer.

35. (Previously Presented) The method of claim 34, wherein the insulating layer contains silicon.

36. (Previously Presented) The method of claim 27, further comprising a step of forming a black matrix layer on the substrate.

37. (Previously Presented) The method of claim 36, wherein the black matrix layer is formed between the substrate and the color filter layer.

38. (Previously Presented) The method of claim 37, wherein the protrusion and the spacer are formed on the black matrix layer.

39. (Previously Presented) A method for manufacturing a liquid crystal display (LCD), comprising steps of:
- forming a black matrix layer on a first substrate, the black matrix layer comprising a first black matrix pattern surrounding a pixel region and a second black matrix pattern formed within the pixel region;
  - forming a color filter layer on the black matrix layer;
  - forming a conductive layer on the color filter layer; and
  - forming a protrusion on a portion of the conductive layer corresponding to the second black matrix pattern, the protrusion having a height to maintain a predetermined gap between the first substrate and a second substrate facing the first substrate.
40. (Previously Presented) The method of claim 39, wherein the height of the protrusion ranges between 3.0  $\mu\text{m}$  and 4.5  $\mu\text{m}$ .
41. (Previously Presented) The method of claim 39, wherein the protrusion is pillar-shaped.
42. (Previously Presented) The method of claim 41, wherein a top surface and a bottom surface of the protrusion have a circular or rectangular shape or a rectangular shape with curved edges.

43. (Previously Presented) The method of claim 39, wherein the protrusion is formed of a photosensitive material, positive or negative photoresist or an insulating material containing silicon.

44. (Previously Presented) The method of claim 39, wherein the pixel region is divided into a plurality of sub-regions and the protrusion is formed within each sub-region.

45. (Previously Presented) The method of claim 44, wherein the protrusion is formed at the center of each sub-region.

46. (Previously Presented) The method of claim 39, wherein the protrusion is in contact with a pixel electrode of the second substrate to maintain the predetermined gap between the first substrate and the second substrate.

47. (New) The method of claim 33, wherein the spacer comprises the insulating layer and the photoresist layer.

48. (New) The method of claim 47, wherein the protrusion comprises the insulating layer.